

Strain and Surface Morphology
in
ZnSe/In_{0.04}Ga_{0.96}As/GaAs(001)
Heterostructures

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Motivation:

Most II-VI blue-green lasers grown on GaAs
(lattice mismatch ZnSe / GaAs: 0.27%)

Active layers: strained ZnSe or ZnCdSe QW

Early degradation is assisted by strain in the
lasing medium

Solution: $\text{In}_x\text{Ga}_{1-x}\text{As}$ lattice matched substrates

Today: ZnSe / $\text{In}_{0.04}\text{Ga}_{0.96}\text{As}$ / GaAs(001)

II-VI	gap	λ [1]	a_0	$\text{In}_x\text{Ga}_{1-x}\text{As}$
ZnSe	2.68 eV		5.668 Å	$x = 0.04$
$\text{Zn}_{0.85}\text{Cd}_{0.15}\text{Se}$	2.49 eV	478 nm	5.726 Å	$x = 0.18$
$\text{Zn}_{0.75}\text{Cd}_{0.25}\text{Se}$	2.37 eV	505 nm	5.764 Å	$x = 0.27$

[1] Hervé et al.: Appl. Phys. Lett. **67** (1995) 2144

Beamline 103 @ ESRF

Surface diffraction

undulator

Monochromator: Si (111) double crystal

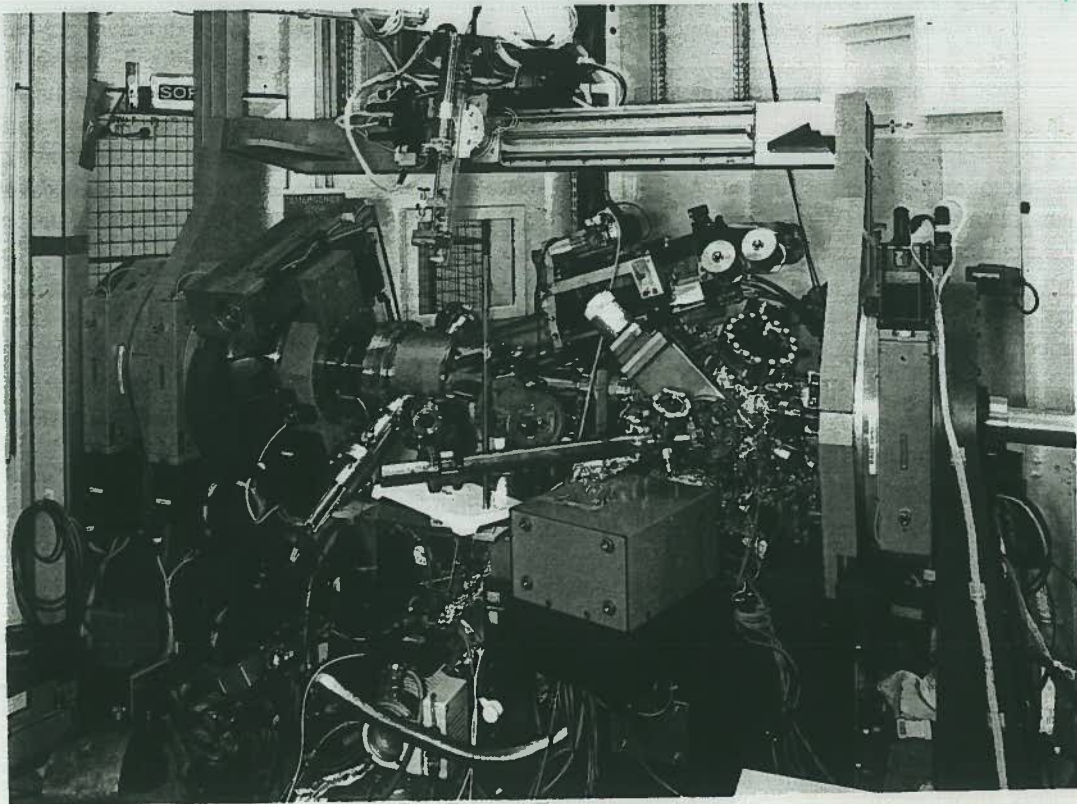
1st: cryo cooled

2nd: horizontal focusing

5-30 keV

$$\Delta E/E \approx 3 \times 10^{-4}$$

flux at sample: $10^{12} \sim 10^{13} \text{ ph s}^{-1}$



ID 3 SURFACE DIFFRACTION

• Beamline 7

at the ESRF

Operational

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beamline tel. +33 76 88 25 99

scientific applications Surface and interface studies

source characteristics

undulator	on a low β section
magnet period:	44 mm
critical energy ϵ_c :	11.8 keV
K_{\max} :	1.85
field B_{\max} :	0.45 T
source size:	0.16 x 0.11 mm ² (HxV) FWHM
source divergence:	210 x 38 μ rad ² (HxV)
peak brightness:	10 ¹⁶ ph s ⁻¹ mrad ⁻² , 0.1%bw, 0.1A (at min. gap)
total power:	0.74 kW
power density at 25 m:	17 Wmm ⁻²
beam size at 30 m:	6.5 x 1.2 mm ² (HxV) FWHM

optics

optical elements:	1st monochr.	2nd monochr.
focusing type:	Si (111) cryocooled	horiz. focusing
demagnification:	2	
ideal beam size at sample:	80 x 30 μ m ² (HxV) focused	
spectral range:	5 - 30 keV	
resolution in $\Delta E/E$:	$\sim 3 \cdot 10^{-4}$	
flux at sample:	$\sim 10^{13}$ ph s ⁻¹ at low energy (0.1%bw, 0.1A)	
	$\sim 10^{12}$ ph s ⁻¹ at high energy (0.1%bw, 0.1A)	

detectors NaI scintillator

beamline control SPEC

ancillary equipment ultra-high vacuum He cryostat, Knudsen cells, electron bombardment evaporator

100nm/300nm ZnSe

BPR=1

**0.27% lattice mismatch
critical thickness: 150nm**

GaAs buffer

GaAs(100)

100nm/300nm ZnSe

BPR=1

2 μ m In_{0.04}Ga_{0.96}As

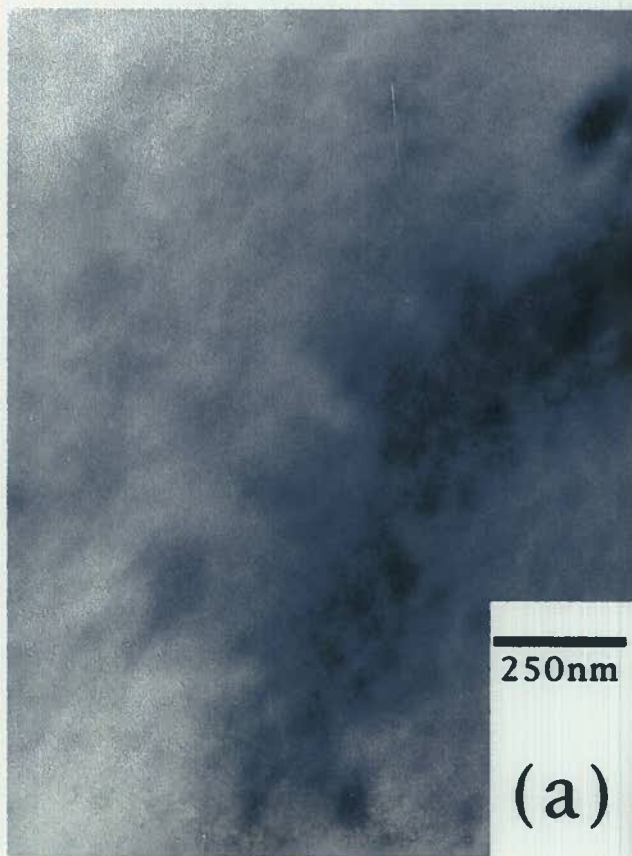
lattice matched to ZnSe

GaAs(100)

pseudomorphic

relaxed

lattice-matched

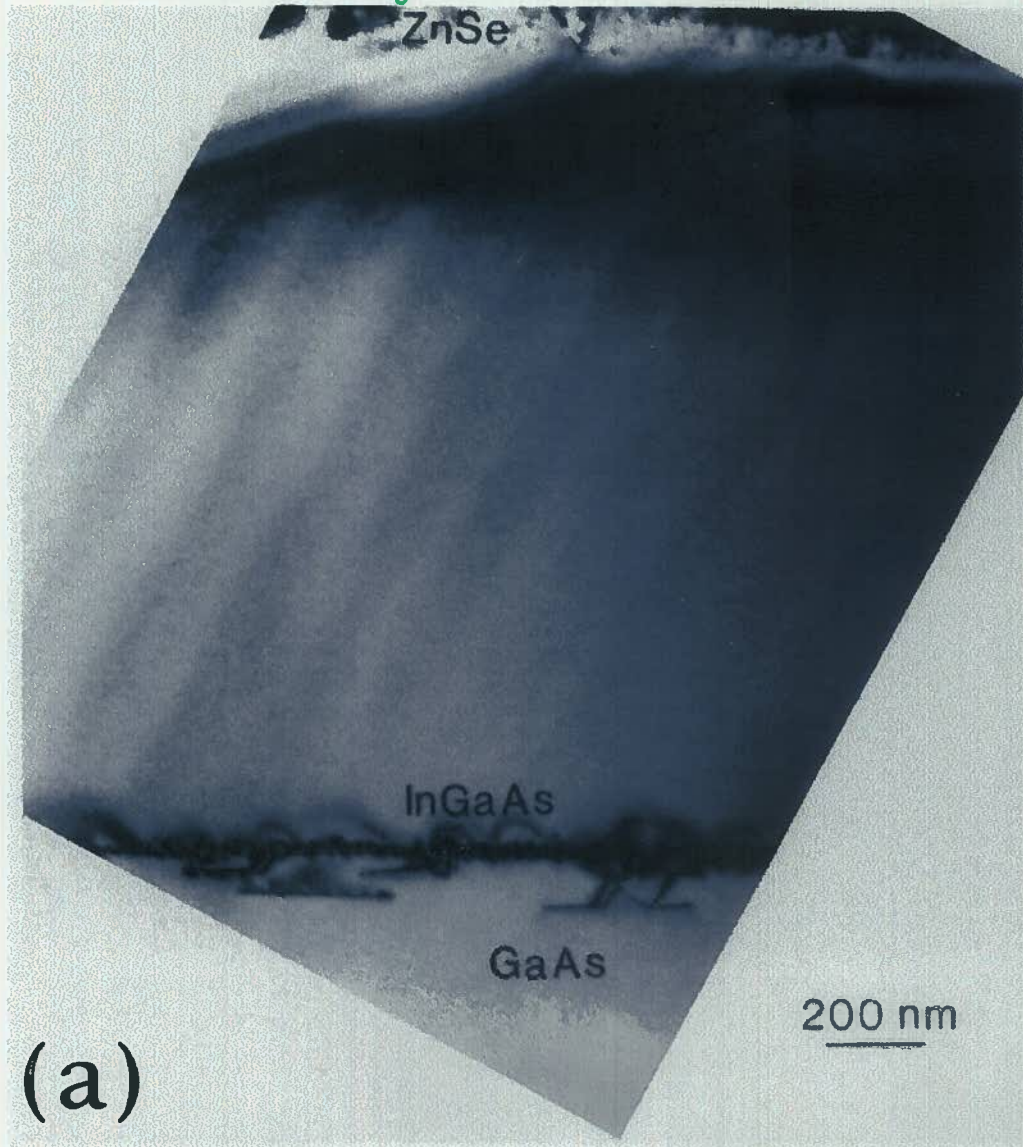


100 nm ZnSe / GaAs

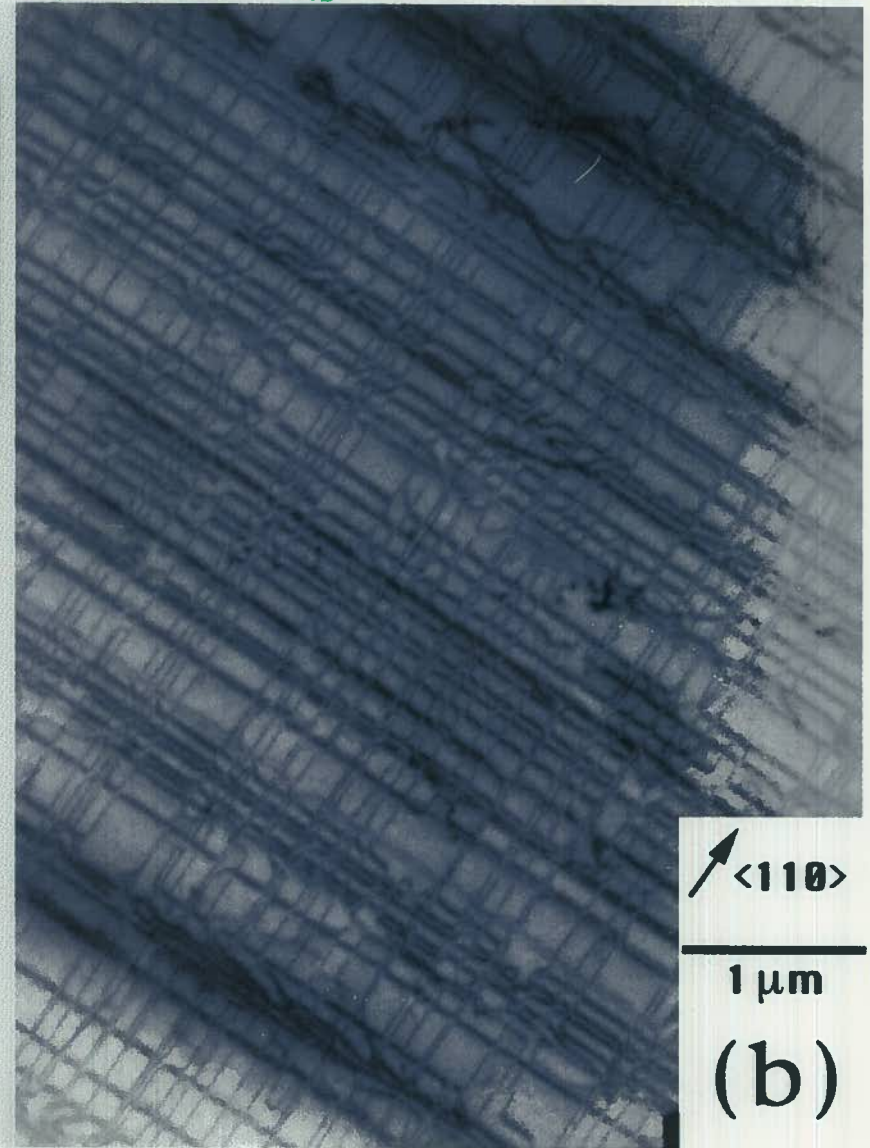
300 nm ZnSe / GaAs

300 nm ZnSe / In_{0.04}Ga_{0.96}As

No threading dislocations ($< 2 \times 10^4 \text{ cm}^{-2}$) $\text{In}_{0.04}\text{Ga}_{0.96}\text{As}$ - buffer relaxed!



(a)



(b)

100 nm ZnSe / 2 μm $\text{In}_{0.04}\text{Ga}_{0.96}\text{As}$ / GaAs (001)

XRD results

300 nm ZnSe / 2 μ m $\text{In}_{0.04}\text{Ga}_{0.96}\text{As}$ / GaAs (001)

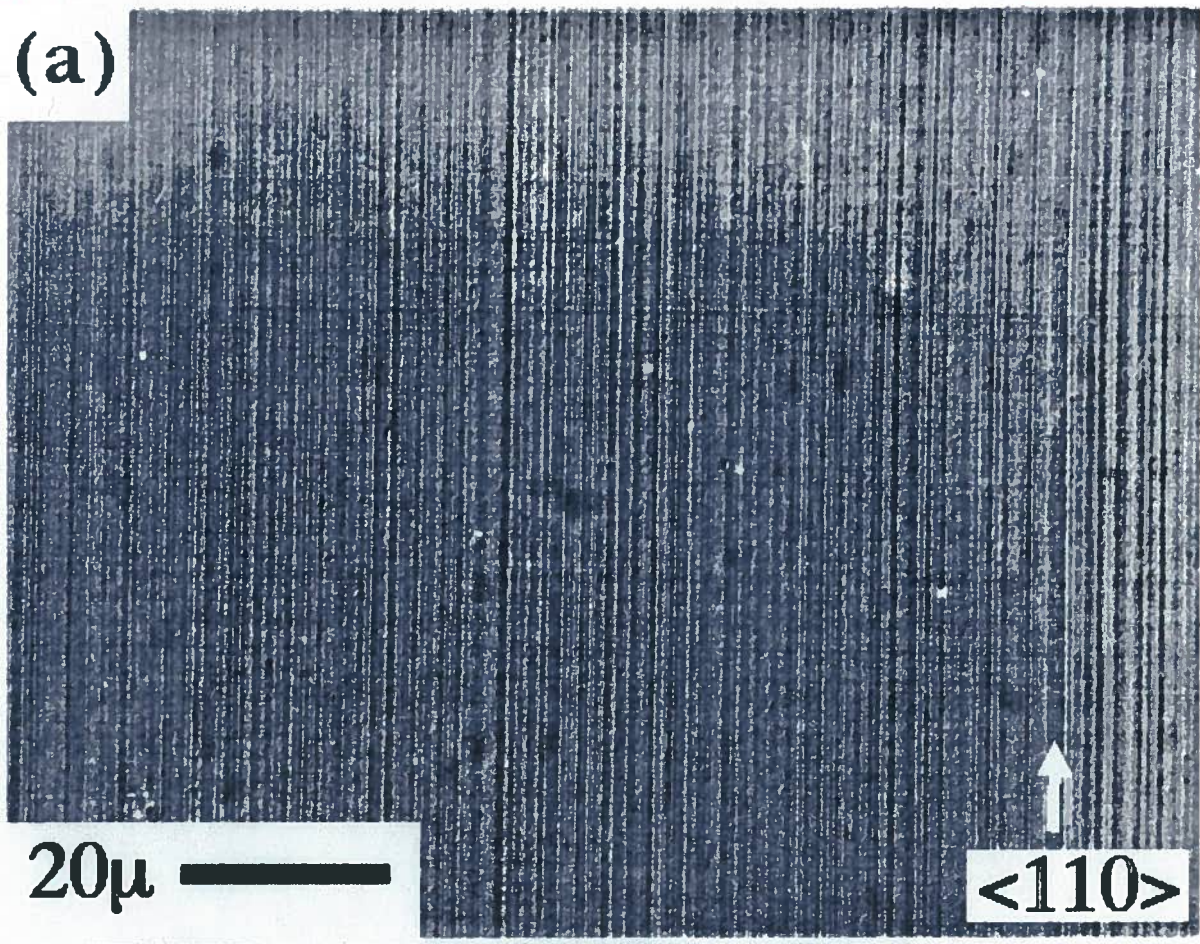
	$\text{In}_x\text{Ga}_{1-x}\text{As}$	ZnSe
a_n [Å]	5.6789 \pm 0.0009	5.6701 \pm 0.0004
a_p [Å]	5.6683 \pm 0.0005	5.6683 \pm 0.0008
a_0 [Å]	5.6738 \pm 0.0007	5.6691 \pm 0.0006
x (XRD)	0.051 \pm 0.002	-----
x (PL)	0.050 \pm 0.002	-----
ϵ_n	0.90×10^{-3}	1.76×10^{-4}
ϵ_p	-0.97×10^{-3}	-1.41×10^{-4}

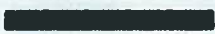
$$\text{GaAs: } a_0 = 5.6533 \text{ \AA}$$

$$\text{ZnSe / GaAs: } \epsilon = 2.72 \times 10^{-3}$$

Nomarski Optical Microscopy

(a)

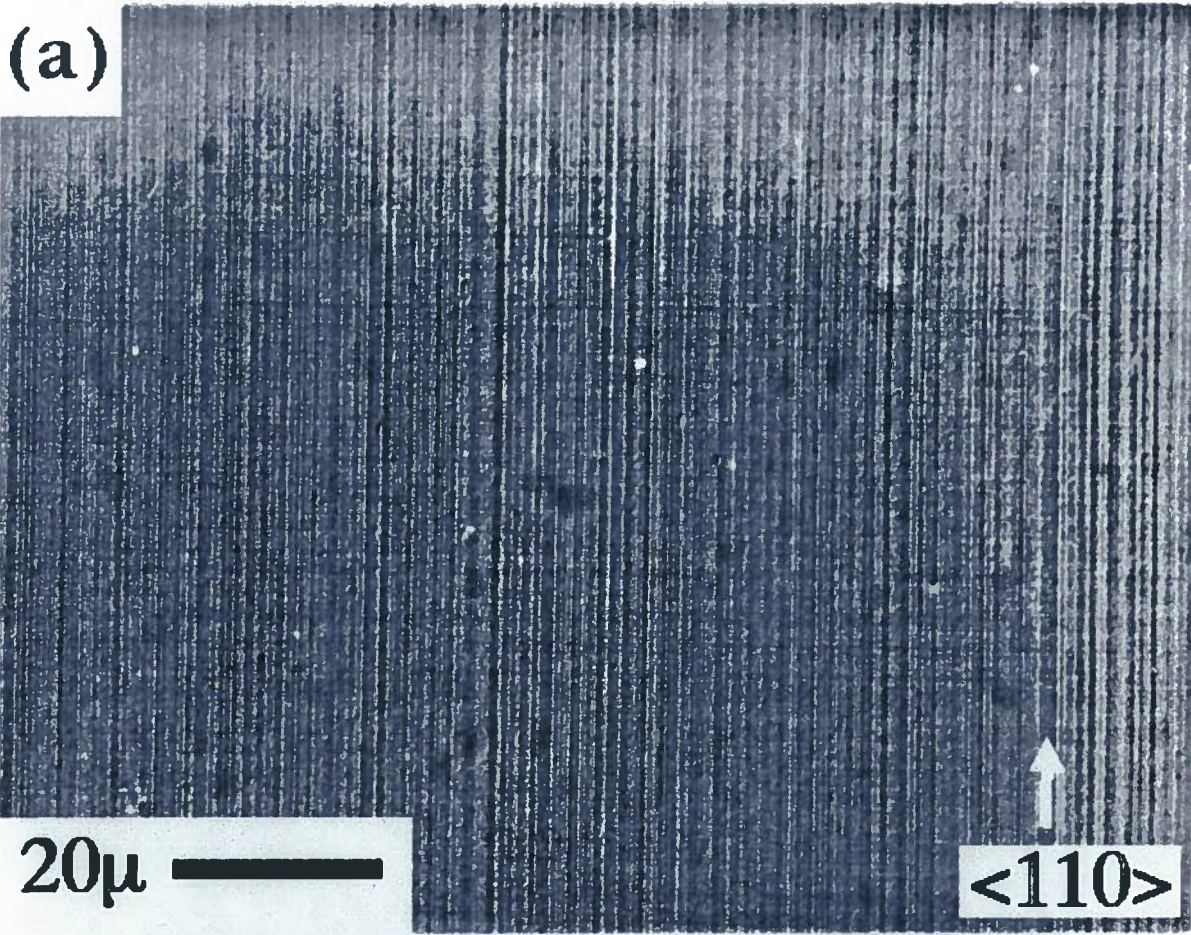


20 μ 

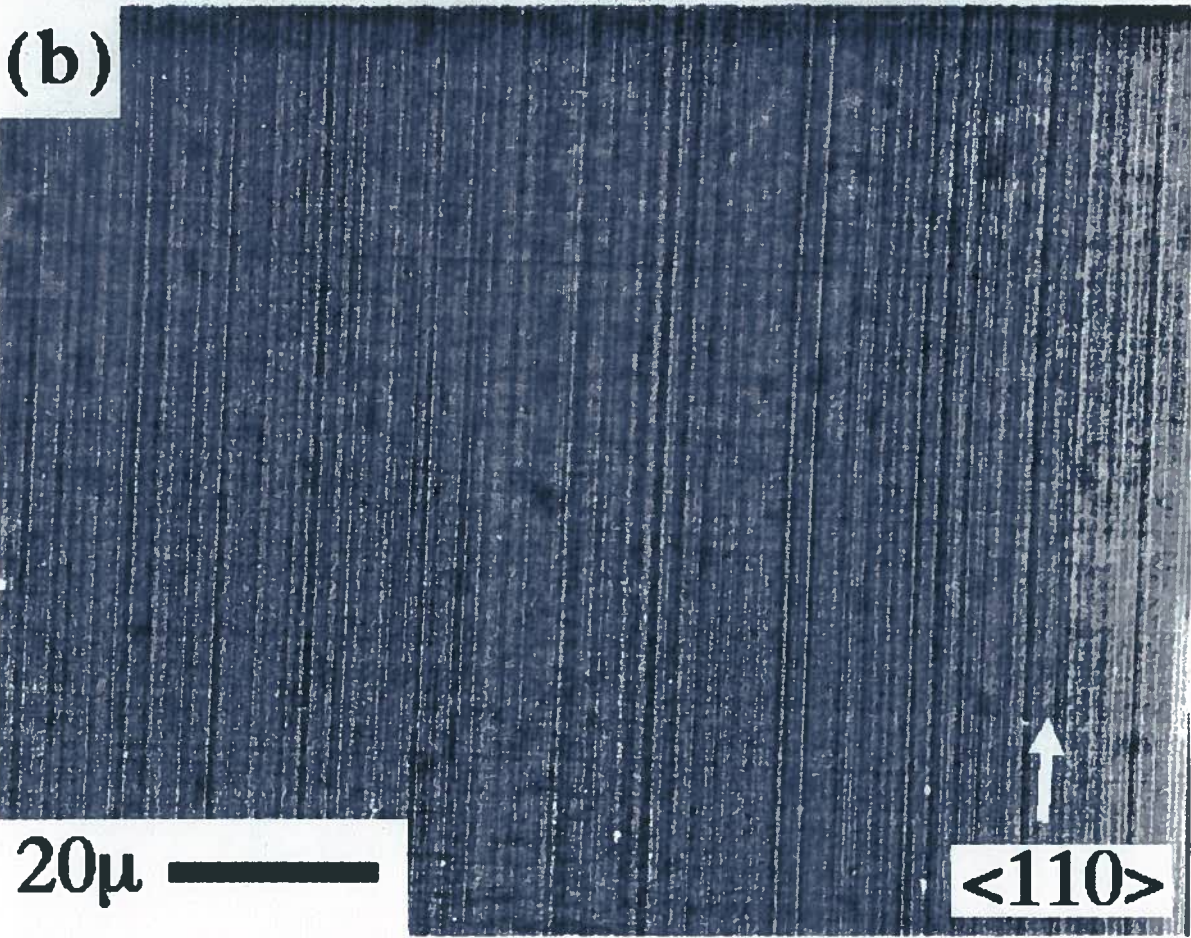
<110>

2 μ m In_{0.04}Ga_{0.96}As / GaAs (001)

Nomarski Optical Microscopy



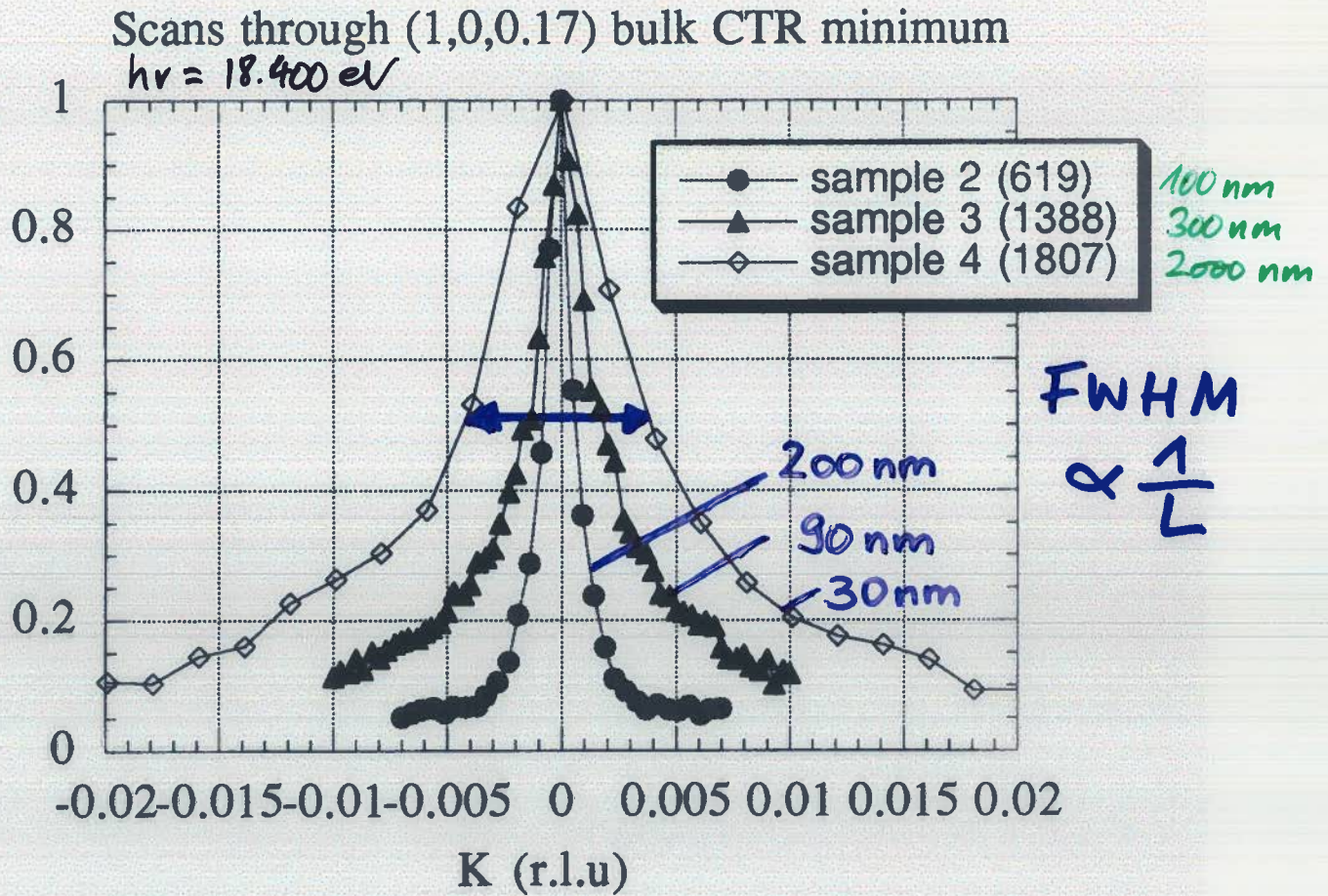
2 μ m In_{0.04}Ga_{0.96}As / GaAs (001)



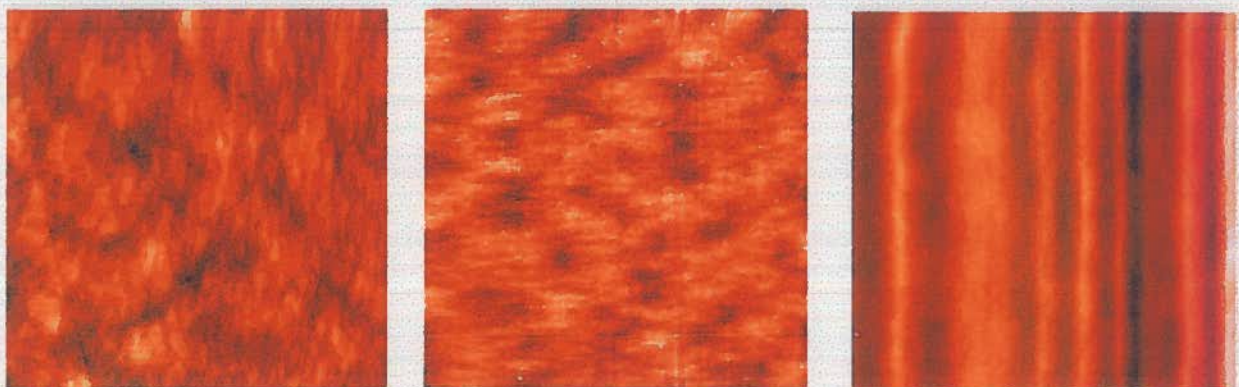
300nm ZnSe / In_{0.04}Ga_{0.96}As

No such cross-hatch for ZnSe / GaAs (001)

Surface XRD @ ESRF



Atomic Force Microscopy

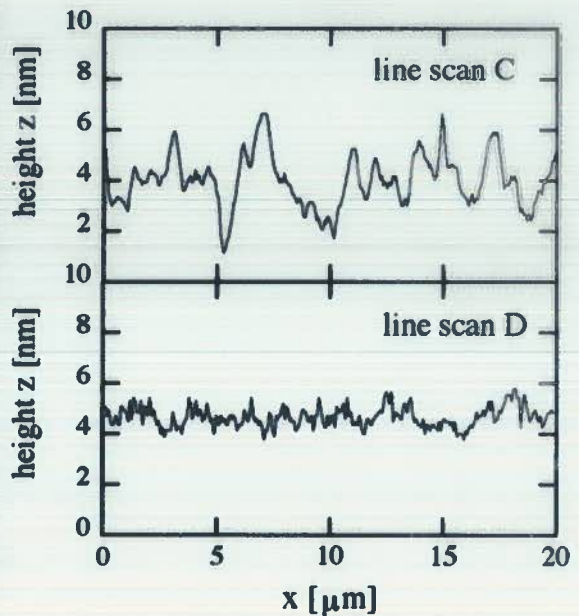
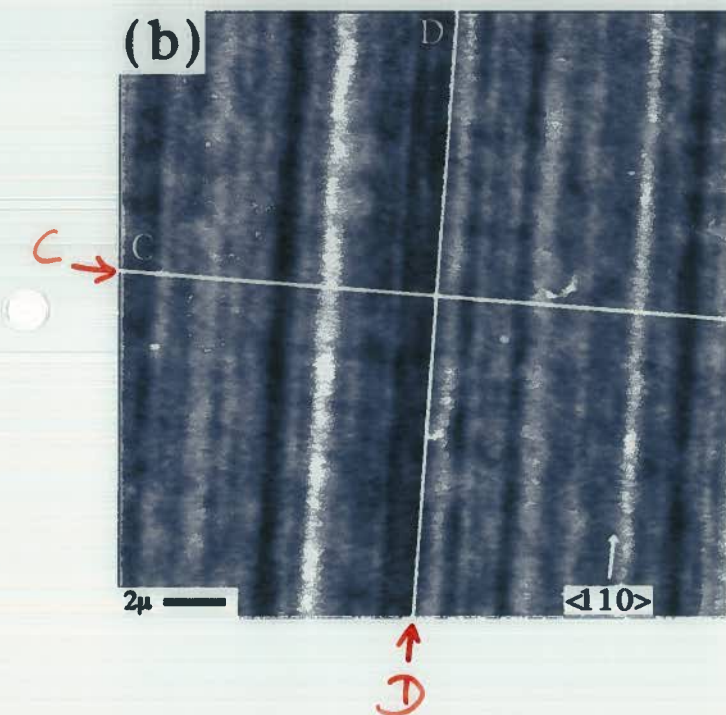
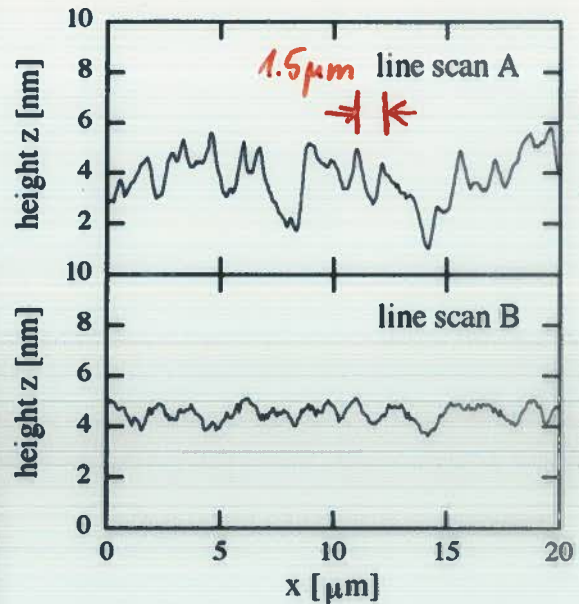
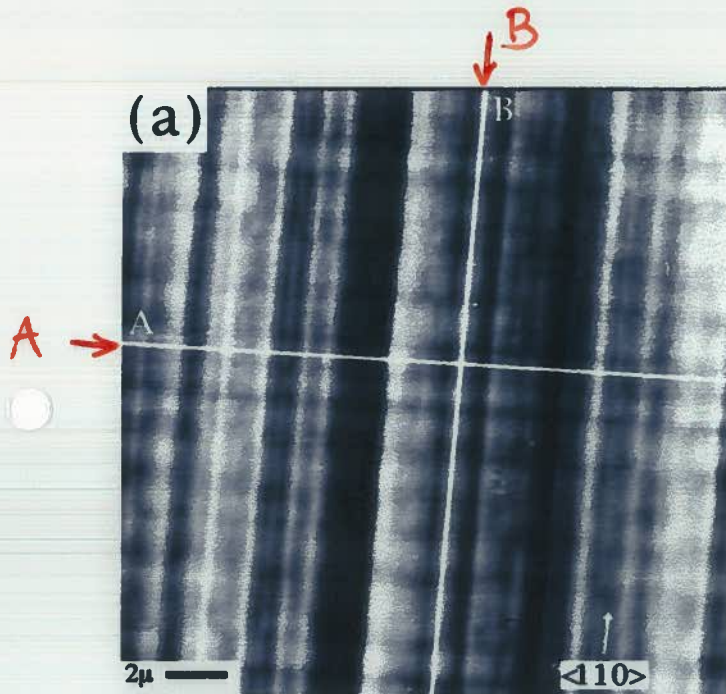


2: 100 nm # 3: 300 nm # 4: 2000 nm

$\text{In}_{0.04} \text{Ga}_{0.96} \text{As}$ on GaAs

RMS- Δ : 2~3 Å 3~4 Å 8 Å

Atomic Force Microscopy



(a) 2μ $\text{In}_{0.04}\text{Ga}_{0.96}\text{As}$ on $\text{GaAs}(001)$

(b) 300nm ZnSe on (a)

$$\Delta_{\text{RMS}} \approx 1\text{nm}$$

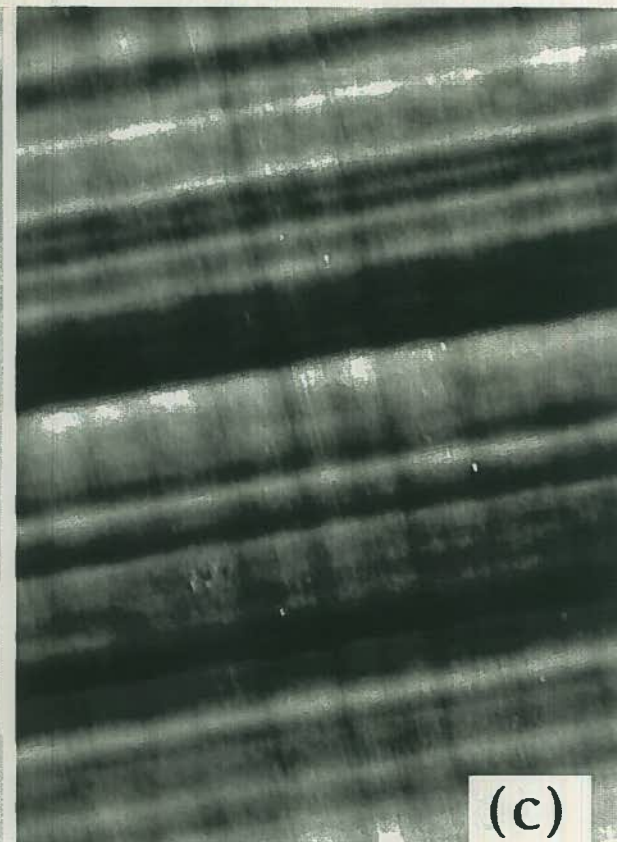
TEM



TEM * Tip

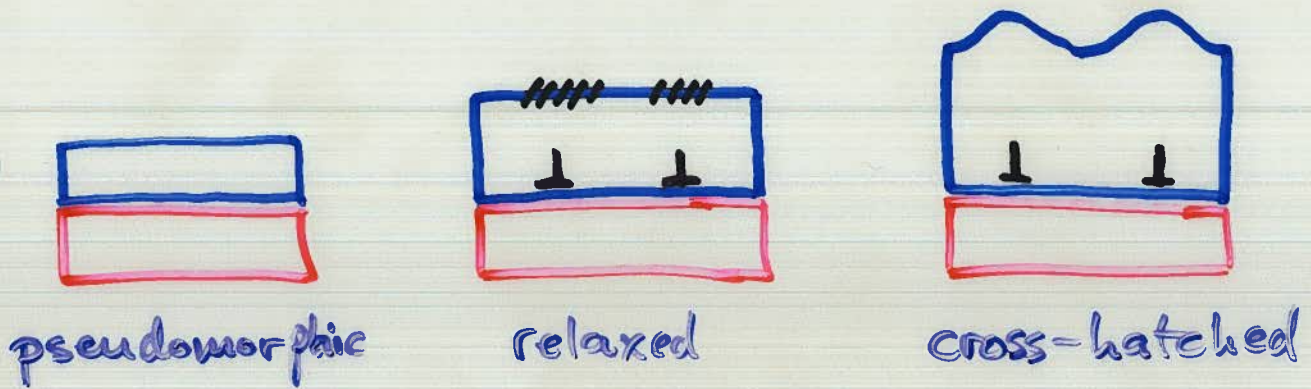


AFM

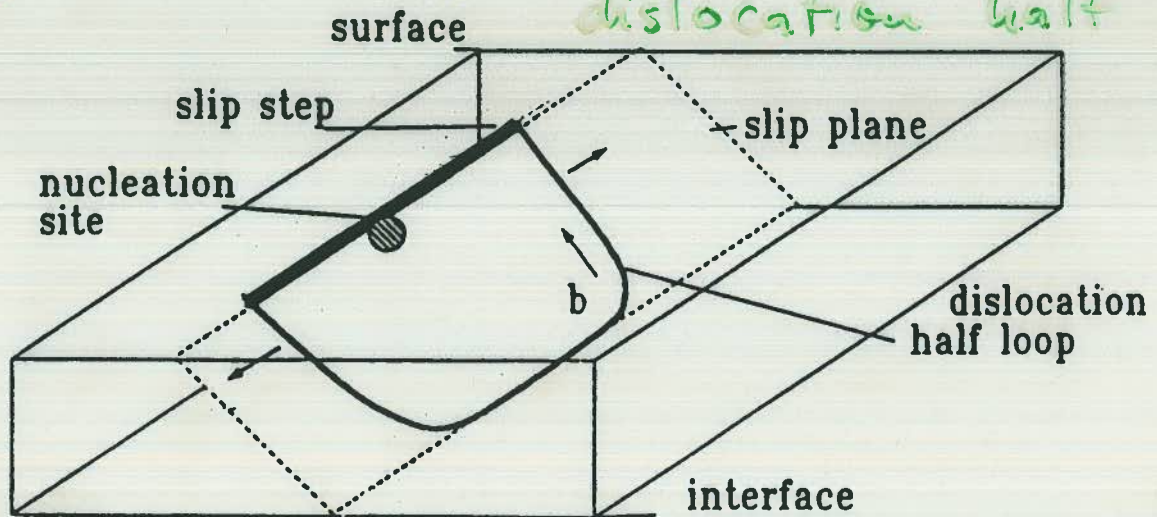


MODELS

(a) local growth rate differences due to dislocations



(b) slip-related surface steps caused by dislocation half loops



TEM: average spacing between dislocations: 100nm

AFM: spacing of surface corrugations: $1.5\mu\text{m}$

$\rightarrow 15$ steps/period \rightarrow height modulation: 2.1nm

AFM: 3nm

Results:

In_{0.04}Ga_{0.96}As - buffer:

dislocation network at the interface to the GaAs

surface corrugation along $\langle 110 \rangle$

corrugations are related to distribution of dislocations

ZnSe / In_{0.04}Ga_{0.96}As:

No misfit and threading dislocations ($< 2 \times 10^4 \text{ cm}^{-2}$)

High bulk structural quality of the II-VI epilayer

surface morphology affected

cross-hatch amplitude 3 nm

period 1 - 2 μm

replicates In_{0.04}Ga_{0.96}As buffer surface